

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Faquir JAIN and Fotios PAPADIMITRAKOPOULIS

Art unit: 1774

Serial No. 09/547,415

Examiner: GARRETT, Dawn

Filed: April 11, 2000

For: FULL COLOR DISPLAY STRUCTURE USING CNC THIN FILM

AMENDMENT (marked-up copy)

Commissioner for Patents P.O. Box 1450 Alenxandria, VA 22313-1450

Sir:

In response to USPTO communication dated Sept. 17, 2003, please amend the application as follows:

IN THE CLAIMS;

Claim 1. (currently amended) A *p-n* junction electroluminescent (EL) device, comprising successive multiple layers of:

- a semiconductor-on-insulator substrate;
- a first p-type Si layer grown on said substrate, part of the layer being oxidized to isolate the electrodes at the bottom of said device;
 - a thin layer of Si thinner than the substrate which allows further epitaxial growth;
 - a second p-type semiconductor layer grown epitaxially;
- a layer comprising pseudomorphic cladded quantum dots nanocrystals (CNCs) with narrower energy gap semiconductor layer than said p-type layer deposited on the said [wide energy gap] $\frac{1}{2}$ second $\frac{1}{2}$ second $\frac{1}{2}$ layer for lattice-matching and electroluminescence;
- [a] an n-type semiconductor layer thinner than the substrate, having [n-type conductivity and] wider energy gap than the cladded quantum dot nanocrystals (CNCs) grown on the CNC layer; and a metal layer forming a plurality of top contact electrodes deposited on the n-type wide energy gap semiconductor layer having patterned regions to confine current conduction in pixels of said EL device.
- Claim 2. (currently amended) The EL device of claim 1, wherein the [thin wide energy gap] second p-type semiconductor layer over said CNC layer is undoped.

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